



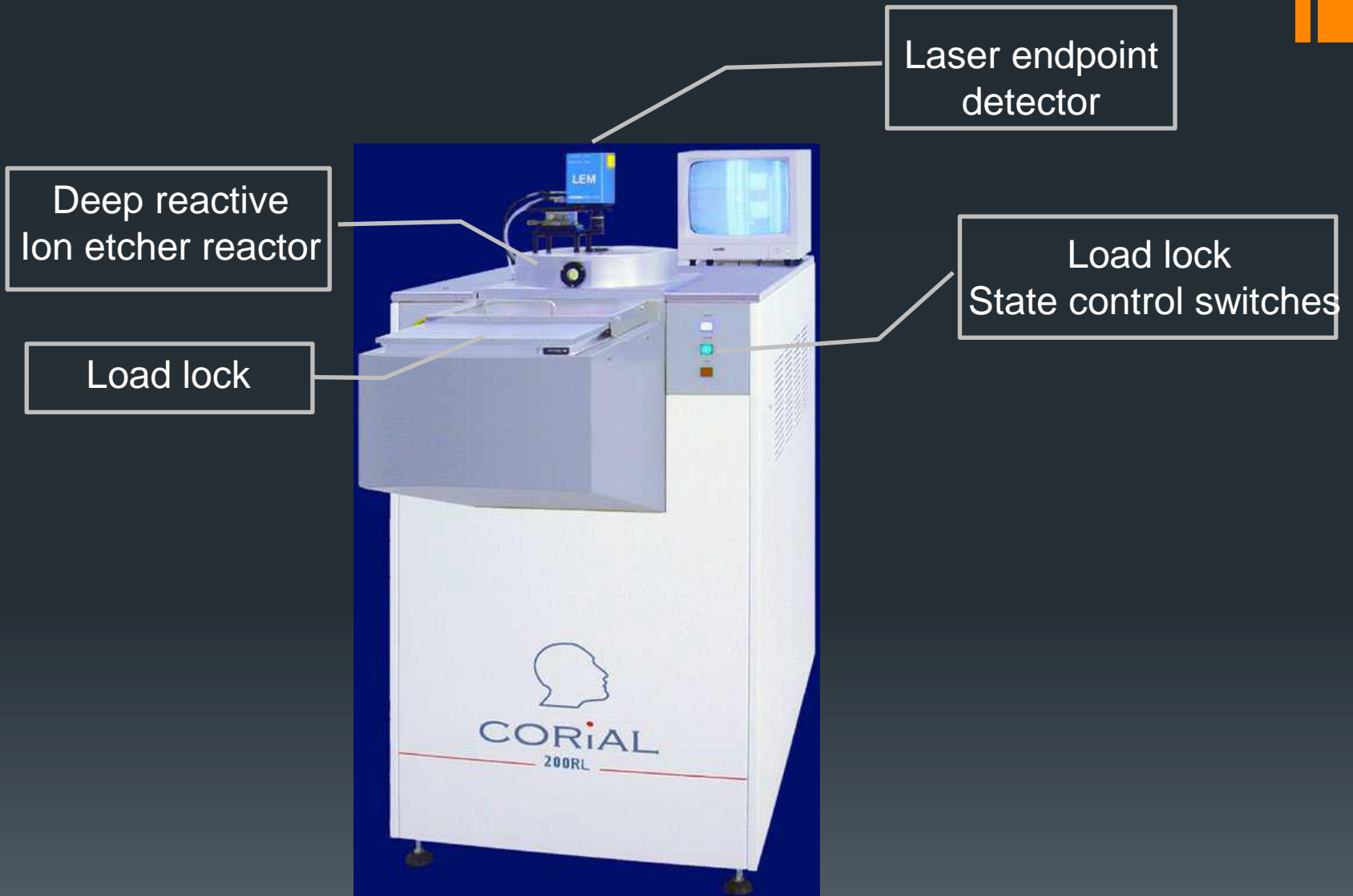
אוניברסיטת בן-גוריון בנגב  
Ben-Gurion University  
of the Negev

מרכז ננו-פבריקציה

# Corial DRIE 200L System

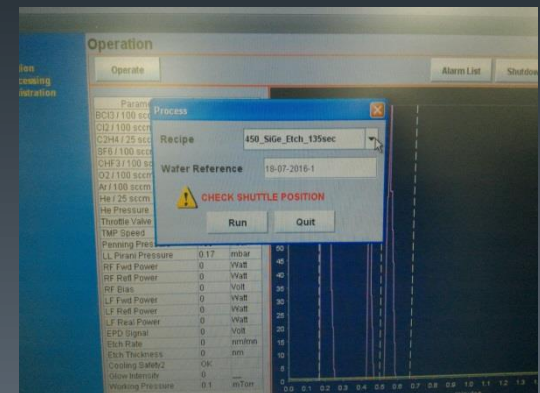
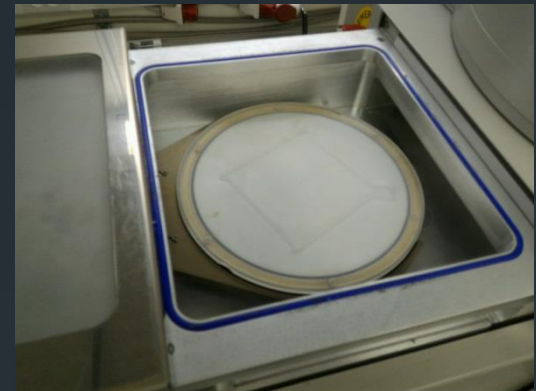


# System Components:



# System operation instructions:

1. !! Insure that the roughing pump powered on. Check that the Nitrogen valve lined to the roughing pump is open. !!
2. If the system is in “Standby” state click “Exit”. If the system is in “Shutdown” state click “Restart”. System will start the TM pump and will go to “Vacuum Ready” state.
3. Press the “Vent” load lock switch. System will go to “Vent” state. Open the load lock door.
4. Gently placing the desired shuttle in place. Confirm that it is placed correctly. Place the substrate at the center of the shuttle.
5. Close the load lock door and press the “Vacuum” load lock switch. System will go to “Vacuum Ready” state. “Operate” button will appear.
6. Click “Operate” to start procedure.



7. Select the desired recipe from the list. Set the wafer reference name in the text field.
8. Click “Run” to start the procedure / “Quit” to cancel the operation.
9. End of process – Click “Save process” to save and exit, “View report” to examine the process and “Quit” to exit without saving.
10. Press the “Vent” load lock switch. System will go to “Vent” state. Open the load lock door.
11. Remove the substrate.
12. Gently remove the shuttle and place it in the cabinet.
13. Close the load lock door and press the “Vacuum” load lock switch. System will go to “Vacuum Ready” state.

End of NORMAL process.

